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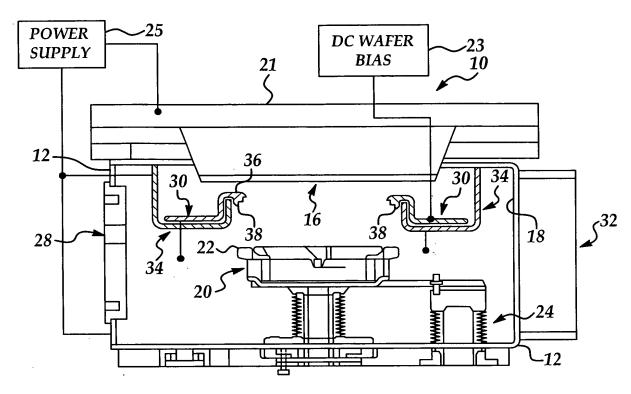
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Serial No.: 09/ 976,082 Filed: 10/12/2001

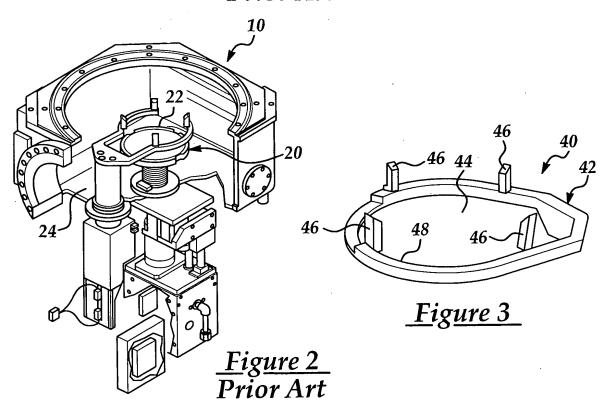
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<u>Figure 1</u> Prior Art



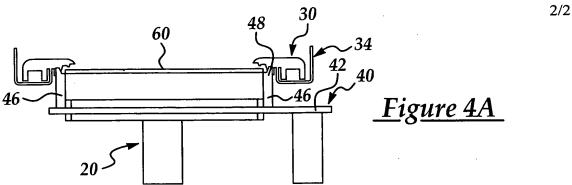


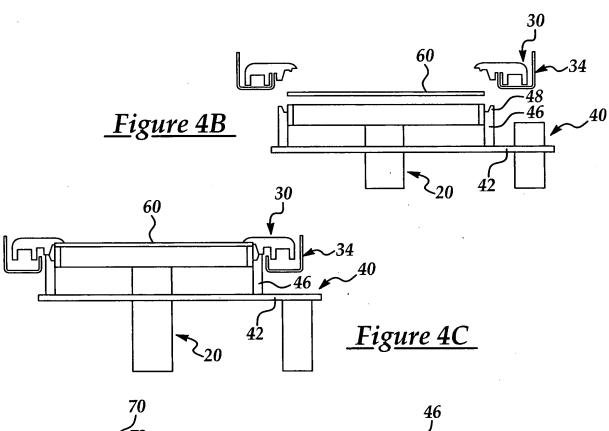
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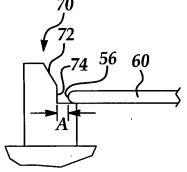


Figure 5A Prior Art

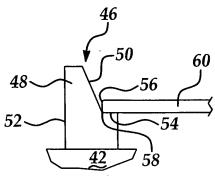


Figure 5B